Deposition of thin conducting films of CuI on glass

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Received 21 January 1998

Abstract

A method is described for coating thin optically transparent conducting films of CuI (p-type semiconductor of band gap ~ 3.1 eV) on glass. The dependence of the sheet resistance of the film on the level of iodine doping and other characteristics of the film are described. A minimum sheet resistance 25 $\Omega/\square$ (for a film of thickness ~ 10 μm) was obtained through an optimization of iodine doping, sintering time and temperature. © 1998 Elsevier Science B.V. All rights reserved.

Keywords: Thin conducting films; CuI; Glass deposition